Status of the JadePix telescope and the CPV chip development

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Outline

- JadePix-3 Telescope *
 - JadePix-3 CMOS chip
 - Prototype of beam telescope
 - Initial test with cosmic rays

- CPV-4 3D integration **
 - 3D-SOI and CPV-4 development
 - Visual inspection on 3D chips
 - Test plan

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R&D of silicon pixel sensor for Vertex (in China)

Targeted on high resolution, low power and fast readout.

CPV-2

- JadePix and TaichuPix on 180 nm CIS process
- CPV on 200 nm SOI process



CPV-3

CPV-4

CPV-1

JadePix-3, a major effort on CMOS pixel sensor

- Technological preparation
 - JadePix-1 on the TowerJazz CIS process
 - JadePix-2 and MIC4 on the design schemes
- Collaborative design of a large team
 - Over 10 participants from IHEP, CCNU, SDU, Dalian Minzu U.
- Test work lasted for 1.5 years to fully characterize the chips
 - Highly required expertise on both sensor and electronics
- Highlighted as the achievements of MOST1 project

The pixel matrix of JadePix-3



Full-sized in the rq direction of detector layout

- Matrix coverage: 16 µm × 512 rows = 8.2 mm
- 4 parallel sectors, scalable in the z direction
 - 48 × 4 = 192 columns

Rolling shutter to avoid heavy logic and routing in pixel matrix

- Minimum pixel size: 16 μm × 23.11 μm
- Matrix readout time: **98.3** µs/frame

Sector	Diode	Analog	Digital	Pixel layout
0	2 + 2 µm	FE_V0	DGT_V0	16×26 µm²
1	2 + 2 µm	FE_V0	DGT_V1	16× 26 µm²
2	2 + 2 µm	FE_V0	DGT_V2	16× 23.11 μm²
3	2 + 2 µm	FE_V1	DGT_V0	16×26 µm²

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Hit processing flow in JadePix-3

Row address extracted from the **row selecting sequence** (Rolling shutter)

Time stamp

Data buffering & transmission

- Column address of HIT encoded at the bottom of matrix
- Only HIT address recorded (zero suppression) <Example of data frame> Time stamp attached to the HIT address Head: Buffer status • In the form of frame number JadePix-3 flow Data: HIT address 1 Data: HIT address 2 row address information extracted Data: HIT address 3 from the row selecting sequence (Rolling shutter) Tail: Frame number col address encoded at the Col. address encoder end of columns
 - Time stamp attached to the generated hit address

Test system for single chip

- 4 test setup deployed in IHEP, CCNU, USTC, JLU IPBUS protocol
 - Used to interact with single JadePix-3 chip
- General-purpose FPGA platform, KC705
 - Well-designed FPGA firmware

- Reliable high-performance control link for particle physics electronics
- JUMBO PACKAGE feature developed to boost the payload data rate up to 750 Mbps



In IHEP Lab





CEPC Workshop, Apr. 2021, Yunpeng Lu

IPBUS: a flexible Ethernet-based control system



Distribution of System Clock

- System clock fanned out from a Si5338 board to all the detector planes
 - Each plane operated in the common clock domain
 - 200 MHz, differential pairs
 - Commercially available





Synchronization of Start Up

Rolling shutter scan to start simultaneously Coincidence of HITs recorded with same frame number strobe sync_start External trigger is not necessary **FSM** IDLE GO Plane 0 configured as Master • To issue a hard-wired start signal Start Start Start Start Start from plane 0 to plane 4 via a daisy chain Plane 4 Plane 3 Slave Plane 2 Slave Plane 1 Slave Plane 0 Slave Master **Clock Generator** Si5338-EVB

Hardware

• Detector plane distance 22 mm

5 detector planes prepared.

• Sensitive area 8.2 mm * 4.8 mm



Threshold

- Threshold calibrated with electrical test pulse
 - 200 e⁻ applied to the full matrix



Noise hit rate

- Noise hit rate below 10⁻⁸ /frame/pixel
 - Low noise rate & Zero suppression resulted in ~100 Bytes / min @ threshold = 200 e⁻
 - \rightarrow long time operation to collect cosmic ray events



Initial test with cosmic ray



More 3-plane events displayed



2-plane events checked

- Number of events sorted according to the combination of planes
 - No event falling in the category "plane 0&2", consistent with the geometry constraints

	plane 0&1	plane 1&2	plane 0&2
Run 119	2	3	0
Run 120	3	1	0
Run 121	4	2	0
Run 122	5	2	0
Run 123	3	1	0
Run 124	0	2	0
Run 125	1	0	0
Sum	18	11	0





To do list

- To complete the integration of 5 detector planes
- **EUTelescope software for track reconstruction and analysis**
 - Need more experts in this area
- Time slot for test beam to be booked or shared
 - Not available yet

Motivation of 3D-SOI development

Vertex Detector

Review report on the Vertex part of CDR in 2018

Findings: there is active R&D and groups are making good progress, building on large effort by the international community. Compared to other efforts toward precise and transparent vertex detectors, CEPC (with its 100% duty cycle) should place stronger emphasis on power management. Advanced processes like 65 nm CMOS or 3D-integrated devices should be pursued actively and can have a big impact on the vertex detector performance.

Pixel to pixel connection is needed to shrink the pixel size \rightarrow spatial resolution 3D-SOI

IO to IO connection is used to shrink the peripheral area \rightarrow 4-side abuttable





Applications	of	3D	in	industry	
	UI	JD	111	muusuy	

3D connection	pixel to pixel	IO to IO
Industrial application	Imaging CMOS	ASIC circuit
Connection	u-Bump	TSV
Stacking	flip chip	top side up
# of layers	2 layers	≥ 2 layers

IO to IO connection

Design resource of 3D-SOI



lower

tier

- 0.2um 3D-SOI process: ~100 transistors and 5 metal layers in each tier
 - lower tier: sensing diode and analog front-end
 - upper tier: digital logic and readout
 - Pixel size can be cut half without compromise of functionality
 - Comparison to the CMOS process
 - 0.35um process: ~10 transistors and 6 metal layers, pixel size ~ 20*20 um²
 - 0.18um process: ~100 transistors and 6 metal layers, pixel size ~ 26*28 um²



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pixel

CPV-4 3D design

Stacking of Sensor + Analog + digital to pursue

CPV4_Upper

- Pixel size 17um * 21um
- Data-driven readout ~ 1us of time stamp
- Power consumption ~ 50mW/cm²



4 pixels arranged in 2 columns



Before 3D integration

- Test on lower and upper tier independently
 - Low leakage current on **sensor** (Diode + Guard Ring)
 - ✓ Signal waveform observed on **analog** front-end
 - ✓ Response from the **digital** logic and readout
- Test system developed and debugged interactively with the upper tier chip





Analog frontend w/o PDD Test charge injected $\sim 100 e^{-1}$



Analog frontend with PDD Test charge injected ~ 750 e⁻



Delivery of 3D chips

- First batch arrived in Aug.
 - Second batch of 17 chips in a couple months



Upper and low tier chips on the wafer



Chips delivered after 3D integration

Visual inspection on 3D chips

Alignment of marks

Lower chip



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Visual inspection on 3D chips

Bonding pad rebuilt on top

3D chip





Visual inspection on 3D chips

Pixel matrix

3D bumps marked with 📃





Lower chip (2*2 pixels)

3D chip (Pattern of upper chip)



Test plan

- Glue and wire bonding on the 3D chips
 - Trial and test with defective samples firstly
- Repeat and compare the tests on lower and upper tier respectively
 - To check possible change on the 3D chips
- Debug and operate the 3D chips as a whole
 - Yield of pixel to pixel connection
 - Electrical calibration
 - Radiative source test
 - Laser test
 - Particle beam test if available



Summary

- JadePix-3 telescope prototype of 3 planes tested with cosmic ray
 - Very low event rate due to the small active area and narrow acceptance angle
 - 3-plane and 2-plane events seemed reasonable
 - Ready to proceed for a 5-plane configuration
- 3D chips for the CPV-4 design were ready for test
 - The essential elements were checked visually
 - Conclusion of test are expected before the end of this year

Thanks for your time





Features of 3D-SOI: low material



- The bulk of upper tier is removed by wet-etching
 - 260 um \rightarrow 10 um thick
 - Wet-etching stopped by the BOX oxide layer automatically → makes SOI quite compatible with 3D integration
- Thinning of the lower tier is also possible
 - 75 um in conventional SOI and 50 um in CMOS (lower tier not necessarily an SOI sensor)

* Currently 3D-SOI demonstrated on a lower tier of 260 um thick

Features of 3D-SOI: TBV



- Backside connection is Through Box Via (TBV)
 - Already established in the SOI process
- Additional metal layer formed for wire bonding
 - Post-process after 3D integration

*Credit of the conceptual drawing: Miho Yamada